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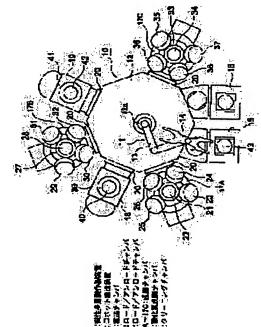
TSUNEKAWA KOJI

(54) MAGNETIC MULTILAYERED FILM DEPOSITION SYSTEM

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a magnetic multilayered film deposition system which has a structure commonly used for the manufacture of TMR device and MRAM and is fitted to the manufacture of a magnetic multilayered film by semiconductor-device manufactures and by which properties of the film can be increased and productivity can be improved.

SOLUTION: In the magnetic multilayered film deposition system 10, each of a plurality of magnetic films is successively deposited in laminated state onto a substrate to deposit the magnetic multilayered film. The magnetic multilayered films are divided into a plurality of groups (A, B, C), and each of the plurality of groups is composed of a plurality of magnetic films which are continuously deposited into laminated state. The plurality of magnetic films contained in each of the plurality of



groups are successively deposited onto a substrate in one and the same film deposition chamber (17A, 17B, 17C), respectively. Film deposition is performed indifferent film deposition chambers for the respective groups.

LEGAL STATUS

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